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AMENDMENT TO THE CLAIMS

Please amend the claims as follows:

Claims 1-16 (Canceled)

17. (Currently Amended) A process for treating a substrate comprising:

at least forming an organic layer on said substrate[[,]]; and
reflowing said organic layer at a substrate temperature from 15 degrees to 40 degrees centigrade.

- 18. (Currently Amended) The process as set forth in claim 17, in which wherein a deformed organic layer is formed from said organic layer in said reflowing, and said deformed organic layer is thinner than said organic layer.
- 19. (Currently Amended) The process as set forth in claim 18, in which wherein said deformed organic layer is equal in thickness to or less than a half third of the thickness of said organic layer.
- 20. (Currently Amended) The process as set forth in claim 17, in which wherein a chemical solution is penetrated into said organic layer so as to dissolve part of said organic layer, thereby reflowing said organic layer.

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21. (Currently Amended) The process as set forth in claim 17, in which wherein a

chemical solution is penetrated into said organic layer so as dissolve part of said organic

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layer for the reflowing, and heat is applied to said organic layer so as to reflow part of said

organic layer.

22. (Currently Amended) The process as set forth in claim 20, in which wherein said

organic layer is exposed to a gaseous mixture of organic solution containing at least

comprising an organic solvent for making said chemical solution penetrate into said

organic layer.

23. (Currently Amended) The process as set forth in claim 21, in which wherein said

organic layer is exposed to a high-temperature ambient at 50-300 degrees centigrade

for applying the heat.

24. (Currently Amended) The process as set forth in claim 22, in which wherein a

temperature of said gaseous mixture ranges from 15 degrees to 40 degrees centigrade.

25. (Currently Amended) The process as set forth in claim 20, in-which wherein a

deformed organic layer produced from said organic layer is thinner than said organic

layer after the reflowing through the dissolution.

26. (Currently Amended) The process as set forth in claim 20, in which wherein said

chemical solution or said organic solution including containing said organic solvent

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comprises an organic solution comprising an containing at least organic solvent selected from the group consisting of alcohols expressed by a general formula of R-OH, alkoxyalcohols, ethers expressed by a general formula of R-O-R, Ar-O-R and Ar-O-Ar, esters, ketones, glycols, alkylene glycols, and glycol ethers where R is an alkyl group or a substituted alkyl group and Ar comprises a phenyl is Phenyl group or an aromatic ring other than except said phenyl group.

- 27. (Currently Amended) The process as set forth in claim 17, in which wherein said organic layer comprises a resist layer.
- 28. (Currently Amended) The process as set forth in claim 18, in which wherein a chemical solution is penetrated into said organic layer so as to dissolve part of said organic layer, thereby reflowing said organic layer.
- 29. (Currently Amended) The process as set forth in claim 19, in which wherein a chemical solution is penetrated into said organic layer so as to dissolve part of said organic layer, thereby reflowing said organic layer.
- 30. (Currently Amended) The process as set forth in claim 18, in which wherein a chemical solution is penetrated into said organic layer so as to dissolve part of said organic layer for the reflowing, and heat is applied to said organic layer so as to reflow part of said organic layer.

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- 31. (Currently Amended) The process as set forth in claim 19, in which wherein a chemical solution is penetrated into said organic layer so as to dissolve part of said organic layer for the reflowing, and heat is applied to said organic layer so as to reflow part of said organic layer.
- 32. (Currently Amended) The process as set forth in claim 21, in which wherein said organic layer is exposed to a gaseous mixture of organic solution comprising an containing at least organic solvent for making said chemical solution penetrate into said organic layer.
- 33. (Currently Amended) The process as set forth in claim 21, in which wherein a deformed organic layer produced from said organic layer is thinner than said organic layer after the reflowing through the dissolution.
- 34. (Currently Amended) The process as set forth in claim 22, in which wherein a deformed organic layer produced from said organic layer is thinner than said organic layer after the reflowing through the dissolution.
- 35. (Currently Amended) The process as set forth in claim 23, in which wherein a deformed organic layer produced from said organic layer is thinner than said organic layer after the reflowing through the dissolution.

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36. (Currently Amended) The process as set forth in claim 24, in which wherein a deformed organic layer produced from said organic layer is thinner than said organic layer after the reflowing through the dissolution.

- 37. (Currently Amended) The process as set forth in claim 21, in which wherein said chemical solution or said organic solution including containing said organic solvent comprises an organic solution comprising an containing at least organic solvent selected from the group consisting of alcohols expressed by a general formula of R-OH, alkoxyalcohols, ethers expressed by a general formula of R-O-R, Ar-O-R and Ar-O-Ar, esters, ketones, glycols, alkylene glycols, and glycol ethers where R is an alkyl group or a substituted alkyl group and Ar comprises a phenyl is Phenyl group or an aromatic ring other than except said phenyl group.
- 38. (Currently Amended) The process as set forth in claim 22, in-which wherein said chemical solution or said organic solution including containing said organic solvent comprises an organic solution comprising an containing at least organic solvent selected from the group consisting of alcohols expressed by a general formula of R-OH, alkoxyalcohols, ethers expressed by a general formula of R-O-R, Ar-O-R and Ar-O-Ar, esters, ketones, glycols, alkylene glycols, and glycol ethers where R is an alkyl group or a substituted alkyl group and Ar comprises a phenyl is Phenyl group or an aromatic ring other than except said phenyl group.

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- 39. (Currently Amended) The process as set forth in claim 18, in which wherein said organic layer comprises a resist layer.
- 40. (Currently Amended) The process as set forth in claim 19, in which wherein said organic layer comprises a resist layer.
- 41. (Currently Amended) The process as set forth in claim 20, in which wherein said organic layer comprises a resist layer.
- 42. (Currently Amended) The process as set forth in claim 21, in which wherein said organic layer comprises a resist layer.
- 43. (Currently Amended) The process as set forth in claim 22, in which wherein said organic layer comprises a resist layer.
- 44. (Currently Amended) The process as set forth in claim 23, in which wherein said organic layer comprises a resist layer.
- 45. (Currently Amended) The process as set forth in claim 24, in which wherein said organic layer comprises a resist layer.
- 46. (Currently Amended) The process as set forth in claim 25, in which wherein said organic layer comprises a resist layer.

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47. (Currently Amended) The process as set forth in claim 26, in which wherein said organic layer comprises a resist layer.